

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

1c971 U.S. PTO
09/944506
08/30/01

In re Application of:

Pai-Hung Pan

Serial No.: Not Yet Assigned

Filed: August 30, 2001

For: TECHNIQUE FOR FORMING
SHALLOW TRENCH ISOLATION
STRUCTURE WITHOUT CORNER
EXPOSURE AND RESULTING
STRUCTURE

Examiner: Unknown

Group Art Unit: Unknown

Attorney Docket No.: 2919.5US (96-499.2)

S. Stevenson
#3
11-20-01

NOTICE OF EXPRESS MAILING

Express Mail Mailing Label Number: EL 740549660 US

Date of Deposit with USPS: August 30, 2001

Person making Deposit: Jared Turner

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
Washington, D.C. 20231

Sir:

The present application is a continuation of application Serial No. 08/789,470, filed January 27, 1997, pending.

Pursuant to M.P.E.P. 2001.06(b), the Examiner is respectfully requested to consider the information of record in the prior applications, and to confirm in the first Office Action on the merits that such art has in fact been reviewed. A PTO-1449 form listing all of the information of record in the prior applications is enclosed herewith.

Attorney Docket: 2919.5US (96-499.2)

This Information Disclosure Statement is filed within three (3) months of the filing date of the above-identified application, and no certification pursuant to 37 C.F.R. § 1.97(c) or a fee pursuant to 37 C.F.R. 1.17(p) is required.

Respectfully submitted,



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Date: August 30, 2001

BGP/ps:djp

Enclosure: Form PTO-1449

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Form PTO-1449

INFORMATION DISCLOSURE CITATION IN AN APPLICATION

(Use several sheets if necessary)

Docket Number (Optional)
2919.5US (96-499.2)

Application Number
Not Yet Assigned

Applicant **Pai-Hung Pan**Filing Date **August 30, 2001**Group Art Unit **Unknown**

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	4,307,180	12/1981	Pogge			
	4,786,954	11/1988	Morie et al.			
	4,849,344	07/1989	Desbiens et al.			
	5,173,439	12/1992	Dash et al.			
	5,272,117	12/1993	Roth et al.			
	5,296,392	03/1994	Gula et al.			
	5,297,082	03/1994	Lee			
	5,346,587	09/1994	Doan et al.			
	5,433,794	07/1995	Fazan et al.			
	5,436,488	07/1995	Poon et al.			
	5,459,096	10/1995	Venkatesan et al.			
	5,492,858	02/1996	Bose et al.			

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO

OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

		Davari, et al., "A Variable-Size Shallow Trench Isolation (STI) Technology With Diffused Sidewall Doping For Submicron CMOS", <i>IEEE IEDM</i> (1988).
		K. Blumenstock et al., "Shallow Trench Isolation for Ultra-Large-Scale Integrated Devices", <i>J. Vac. Sci. Technol.</i> , B 12(1) (Jan/Feb 1994).

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.



Form PTO-1449

INFORMATION DISCLOSURE CITATION
IN AN APPLICATION

(Use several sheets if necessary)

Docket Number (Optional)
2919.5US (96-499.2)Application Number
N t Yet AssignedApplicant **Pai-Hung Pan**Filing Date **August 30, 2001**Group Art Unit **Unknown**

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	5,506,168	04/1996	Morita et al.			
	5,516,625	05/1996	McNamara et al.			
	5,516,721	05/1996	Galli et al.			
	5,521,422	05/1996	Mandelman et al.			
	5,677,233	10/1997	Abiko			
	5,683,932	11/1997	Bashir et al.			
	5,712,185	01/1998	Tsai et al.			
	5,801,083	09/1998	Yu et al.			
	5,811,346	09/1998	Sur et al.			
	5,834,358	11/1998	Pan et al.			
	5,960,297	09/1999	Saki			

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO

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(Including Author, Title, Date, Pertinent Pages, Etc.)

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